

	Hit s	Search Text	DBs
26	18	((sensor or detector or interferometer or microscope or SEM) same (mitigat\$4 or reduc\$4 or decreas\$4 or chang\$4 or alter\$4 or correct\$4) same (detect\$4 or monitor\$4 or respons\$4 or sens\$5) same (line\$4edge\$4roughness or ((edge or side\$4) near12 roughnes\$4) or LER or (line\$3 near3 edge near4 roughnes\$3)) same (pattern or ((resist or photoresist) near9 (structure or pattern\$4 or feature))))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
27	51	((sens\$3 or detect\$4 or interferomet\$4 or microscope or SEM) same (mitigat\$4 or reduc\$4 or decreas\$4 or chang\$4 or alter\$4 or correct\$4) same (detect\$4 or monitor\$4 or respons\$4 or sens\$5) same (line\$4edge\$4roughness or ((edge or side\$4) near12 roughnes\$4) or LER or (line\$3 near3 edge near4 roughnes\$3)) same (pattern or ((resist or photoresist) near9 (structure or pattern\$4 or feature))))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
28	2	<p>((selective\$5 or response or signal\$4 or (defect near9 portion)) same (sensor or detect\$4 or interferomet\$4 or microscop\$3 or SEM) same (mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post\$4heat\$4 or heat\$4) same (line\$3dege\$3roughness or ((edge or side\$4) near12 roughnes\$4) or LER or (line\$3 near3 edge near4 roughnes\$3)) same (pattern or ((resist or photoresist or photosensitive) near9 (structure or pattern\$4 or feature)))) and (((trim\$4 near5 etch\$4) or trim\$5 or etch\$5) same (CD or (critical near5 dimension)))</p>	<p>US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB</p>